



FINAL DRAFT International Standard

ISO/FDIS 21068-4

Chemical analysis of raw materials and refractory products containing silicon-carbide, silicon-nitride, silicon-oxynitride and sialon —

Part 4: XRD methods

*Analyse chimique des matières premières et des produits
réfractaires contenant du carbure de silicium, du nitrure de
silicium, de l'oxynitride de silicium et du SiAlON —*

Partie 4: Méthodes de DRX

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Introduction

The ISO 21068 series has been developed from the combination of EN 12698-1:2007 [1] and EN 12698-2:2007 [2] and ISO 21068-1:2008,[3] ISO 21068-2:2008 [4] and ISO 21068-3:2008.[5] The latter has been originally developed from the combination of Japanese standard JIS R 2011:2007 [6] and work items developed within CEN. Because there is a wide variety of laboratory equipment in use, the most commonly used methods are described.

This document is derived from EN 12698-2:2007[2] describing XRD methods for the determination of mineralogical phases typically apparent in nitride and oxy-nitride bonded silicon carbide refractory products using a Bragg-Brentano diffractometer.

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